

## EUROPEAN PATENT OFFICE

## Patent Abstracts of Japan

PUBLICATION NUMBER : 01136969  
PUBLICATION DATE : 30-05-89

RECEIVED  
CENTRAL FAX CENTER

APPLICATION DATE : 24-11-87  
APPLICATION NUMBER : 62295453

SEP 05 2003

APPLICANT : MITSUBISHI METAL CORP;

INVENTOR : MARUYAMA HITOSHI;

INT.CL. : C23C 14/34

TITLE : MANUFACTURE OF TARGET FOR TITANIUM SILICIDE SPUTTERING

ABSTRACT : PURPOSE: To manufacture a good target having less segregation of its structure and oxygen contents at the time of manufacturing said target by melting Ti and Si in a nonoxidizing atmosphere into alloy, thereafter grinding it and subjecting said powder to hot pressing.

CONSTITUTION: Pure Si powder, 38.7wt.%, and 61.3wt.% Ti plate are jointly charged to a water-cooling Cu hearth; vacuum drawing is executed thereto and the Si powder and Ti plate are melted to cast Ti-Si alloy. The ingot of said Ti-Si alloy is ground and sieved, by which the target of titanium silicide is manufactured by hot pressing with that having 50-500 $\mu$ m average grain size. The target of titanium silicide having less segregation of components and oxygen contents inside of the target and further having excellent strength can be obtd.

COPYRIGHT: (C)1989,JPO&Japio

OFFICIAL